

QUERY CONTROL FORM		RTIS USE ONLY	
Application No. <u>091550990</u>	Prepared by <u>J. McGill</u>	Tracking Number <u>60060338</u>	
Examiner-GAU <u>Lee - 2811</u>	Date <u>9-27-04</u>	Week Date <u>9-6-04</u>	
	No. of queries <u>1</u>	IFW	

JACKET			
a. Serial No.	f. Foreign Priority	k. Print Claim(s)	p. PTO-1449
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other

[illegible]

LIST OF REFERENCES CITED BY APPLICANT (Use several sheets if necessary)				ATTY. DOCKET NO. Y0996-118X		SERIAL NO.	
				APPLICANT: Kevin K. Chan et al.			
				FILING DATE: HEREWITH		GROUP:	
U.S. PATENT DOCUMENT							
Examiner Initial	Document Number	Date	Name	Class	Sub- Class	Filing Date	
AA	5,405,787	04/95	Kazumi Kurimoto	H01L	21/265	10/14/93	
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AO	TW 205579	07/95	Taiwan			Abstract	
AP							
OTHER REFERENCES (Including author, title, date, pertinent pages, etc.)							
AR	A. Acovic et al., "Novel Gate Process for 0.1 Micron MOSFETs", IBM Technical Disclosure Bulletin, Vol. 36, No. 11, November 1993.						
AS							
AT							
EXAMINER				DATE CONSIDERED			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							